The Development and the commercialization of the Mask Aligner for wafer Midas System will continue to grow along with the value creation for our customers,





The MIDAS MDA-600S Mask aligner is good for research and variable process of all applications. It represents next generation of full-field lithography systems.



ITEM	SPECIFICATIONS
Substrate Size	Up to 6" diameter
UV Lamp Power	350W Lamp(350-450nm) or UV LED(365nm)
Uniform Beam Size	6.25" \times 6.25" or 160mm diameter, \pm 2% of Uniformity
365nm Beam Intensity	$20-30 \text{mW/cm}^2$ or $\leq 22 \text{mW/cm}^2$
Options	BSA, UV-LED, Namo-imprint



589, Yongsan-dong, Yuseong-gu, Daejeon, 305-500, Korea
Tel: +82-42-936-7620 / Fax: +82-42-936-7623 / A/S Center: +82-1544-7618

Homepage: www.aligner.co,kr/www.midas-system.com